Kanagasabapathy et al. U.S.S.N. 10/690,835 Page 2

This listing of claims will replace all prior versions of claims in the application.

Claims 1-20. (cancelled)

Claim 21. (currently amended) A positive photoresist composition comprising:

- i) a photoactive component;
- ii) a first polymer that is a silsesquioxane and comprises one or more Si atoms; and
- iii) a second polymer that comprises one or more sulfonamide groups.
- Claim 22. (previously presented) A photoimageable composition of claim 21 wherein at least one of the first and second polymers comprises photoacid-labile groups.
- Claim 23. (previously presented) A photoimageable composition of claim 21 wherein the at least one of the first and second polymers comprises aromatic groups.
- Claim 24. (previously presented) A photoimageable composition of claim 21 wherein the first and second polymer are at least substantially free of aromatic groups.

Claims 25-31. (cancelled)

Claim 32. (currently amended) A positive phototoimageable composition comprising:

one or more photoacid generator compounds;

at least one polymer that is a silsesquioxane and comprises at least three distinct repeat units, wherein one or more repeat units comprise one or more photoacid labile groups;

and the polymer or one or more other components comprises one or more Si atoms and one or more sulfonamide groups.

Kanagasabapathy et al. U.S.S.N. 10/690,835 Page 3

- Claim 33. (previously presented) The photoimageable composition of claim 32 wherein the one or more of the polymer repeat units comprise one or more photoacid labile groups.
- Claim 34. (previously presented) The photoimageable composition of claim 32 wherein the polymer comprises one or more Si atoms and one or more sulfonamide groups.
 - Claim 35. (cancelled)
- Claim 36. (previously presented) The photoimageable composition of claim 32 wherein the polymer comprises aromatic groups.
- Claim 37. (previously presented) The photoimageable composition of claim 32 wherein the polymer is at least substantially free of aromatic groups.
- Claim 38. (previously presented) A method for forming a electronic device, comprising:
 - (a) applying on a substrate a coating layer of a polymer composition;
- (b) above the polymer composition coating layer, applying a photoimageable composition of claim 21;
- (c) exposing the photoimageable composition coating layer to activating radiation and developing the exposed photoimageable layer.

Claim 39. (cancelled)

Kanagasabapathy et al. U.S.S.N. 10/690,835 Page 4

Claim 40. (previously presented) A method for forming a electronic device, comprising:

- (a) applying on a substrate a coating layer of a polymer composition;
- (b) above the polymer composition coating layer, applying a photoimageable composition of claim 32;
- (c) exposing the photoimageable composition coating layer to activating radiation and developing the exposed photoimageable layer.